

5 Rec'd PCT/PTO 11 JAN 2005

FORM PTO-1449	Docket No.: I435.121.101/12307US	Serial No. / Unknown Priority Appln. No. DE 102 31 407.1 Int'l Appln. No. PCT/EP2003/007553
	LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	
Applicant: Josef Böck et al.		
Filing Date: Herewith Priority Date July 11, 2002 Int'l Filing Date July 11, 2003		Group Art: Unknown

## U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
SWL	4,437,897	03/1984	Kemlage			
	5,049,964	09/1991	Sakai et al.			
	5,407,857	04/1995	Higuchi			
	5,541,444	07/1996	Ohmi et al.			
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SWL	6,800,881	10/2004	Lippert et al.			

## FOREIGN PATENT DOCUMENTS

	Document No.	Date	Country	Class	Sub Class	Translated Yes No
SWL	0 646 952	04/1995	EPO			Yes
SWL	00/13206	08/1999	PCT			Yes
SWL	2004/008543	01/2004	PCT			Yes

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

SWL	Lumng Shehng Lee et al., "Argon Ion-Implantation on Polysilicon or Amorphous-Silicon for Boron Penetration Suppression in p + p MOSFET" August 1998, IEEE Transactions on Electron Devices, pgs. 1737-1744.

EXAMINER: CRANE DATE CONSIDERED: 3/2006

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.